

**REMARKS**

Claims 1-6 are pending in this application. By this Amendment, claims 1, 3 and 5 are amended. No new matter is added by these amendments. Reconsideration of the application based upon the above amendments and the following remarks is respectfully requested.

The Office Action, on page 2, rejects claims 1, 3 and 5 under 35 U.S.C. §103(a) as being unpatentable over U.S. Patent No. 5,570,506 to Tawata et al. (hereinafter "Tawata") in view of U.S. Patent No. 4,336,100 to Passlick. Additionally, the Office Action, in paragraph 3, rejects claims 2, 4 and 6 under 35 U.S.C. §103(a) as being unpatentable over Tawata in view of Passlick, and further in view of U.S. Patent No. 6,180,261 to Inoue et al. (hereinafter "Inoue"). The Applicants respectfully traverse these rejections.

The Office Action concedes that Tawata fails to disclose patterning an upper circuit layer on the polyimide layer by a semi-additive technique. The Office Action relies on Passlick to overcome this deficiency of Tawata.

Tawata teaches a method for forming multi-layer wiring construction. As such, Tawata teaches building upon a polyimide precursor layer, based upon a metal layer of alumina, and forming an upper circuit layer on the polyimide precursor layer. However, Tawata does not teach that the polyimide precursor layer is partially exposed at the upper circuit layer side. Tawata teaches that the polyimide precursor layer is exposed on the sides of the polyimide precursor layer, and not on the upper circuit layer side, as positively recited in amended claims 1, 3 and 5. Any permissible combination of Passlick and/or Inoue with Tawata does not overcome this deficiency of Tawata as applied to the subject matter of the pending claims.

For at least the above reason, Tawata, Passlick and Inoue cannot reasonably be considered or to have suggested the combinations of all of the features recited in at least independent claims 1, 3 and 5. Further, claims 2, 4 and 6 would also not have been suggested

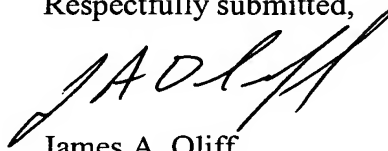
by the applied prior art references for at least the respective dependence of these claims on allowable independent claims 1, 3 and 5, as well as for the separately patentable subject matter that each of these claims recite.

Accordingly, reconsideration and withdrawal of the rejections of claims 1-6 under 35 U.S.C. §103(a) as being unpatentable over any permissible combination of the applied prior art references are respectfully requested.

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 1-6 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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Attachment:  
Request for Continued Examination

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